

SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED
OXYNITRIDE.....

Gary Chen et al.

Appl. No.: Unknown

Atty Docket: MICRON.109DC1D1

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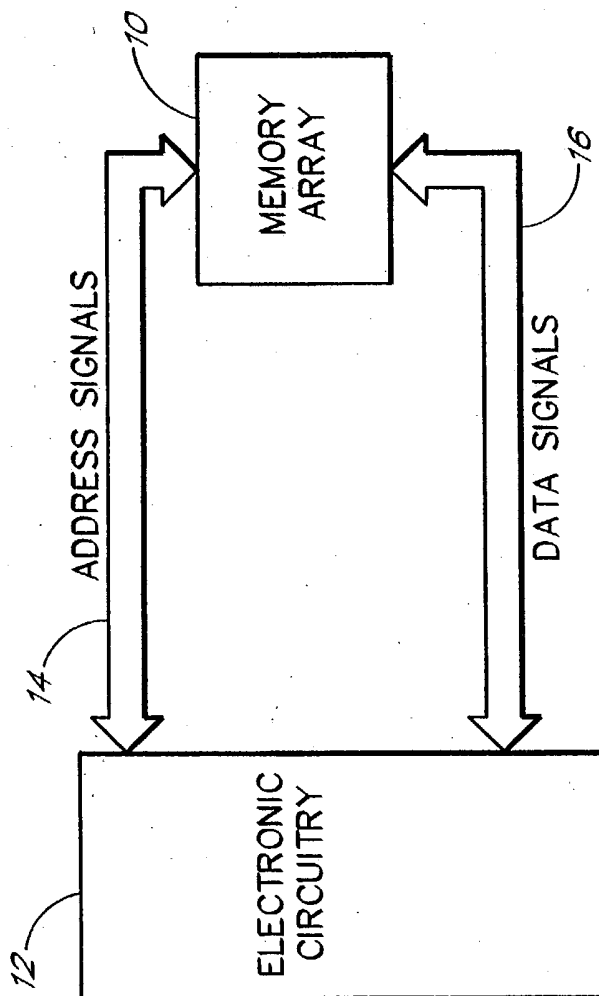


FIG. 1

SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED
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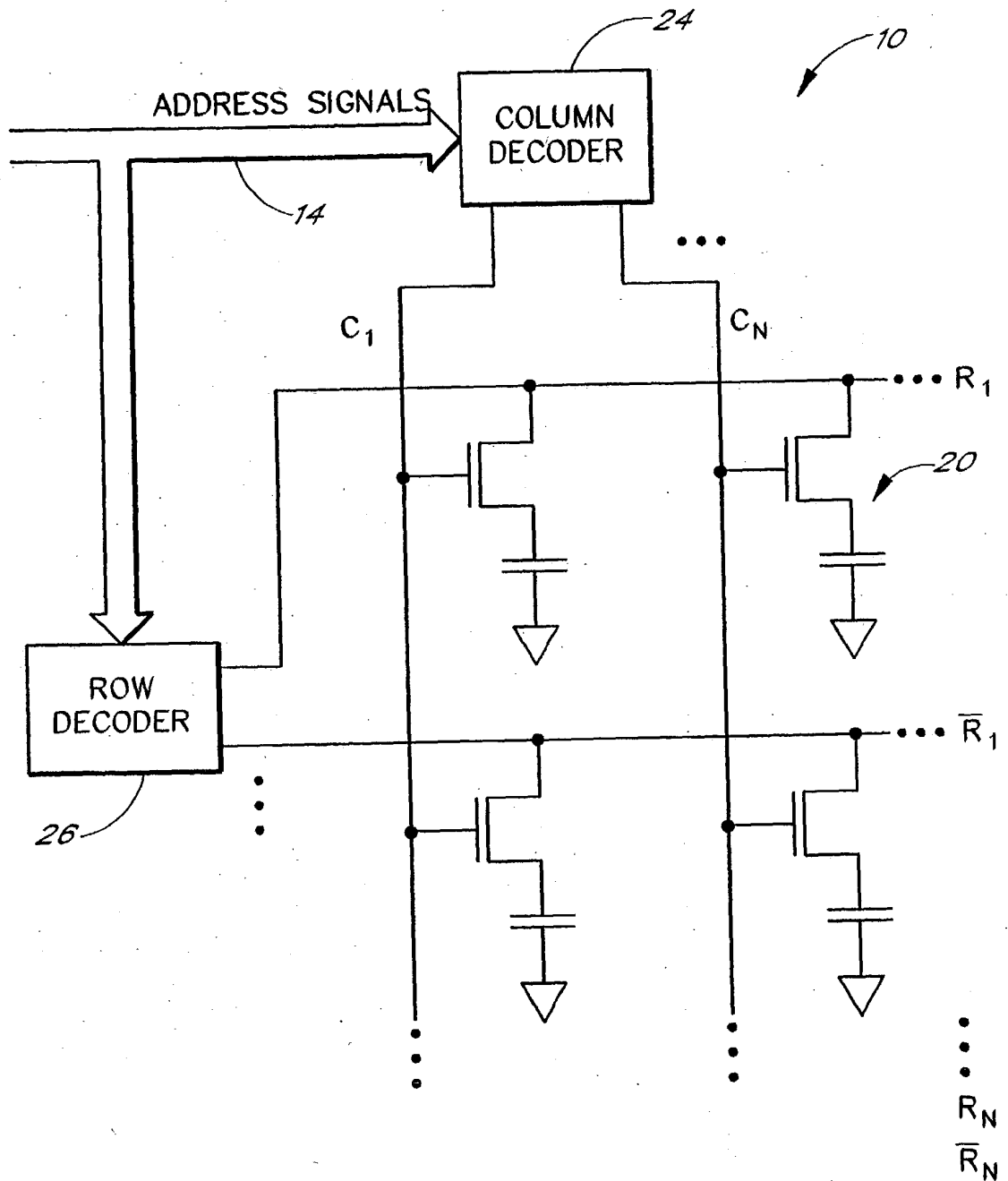


FIG. 2

SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED
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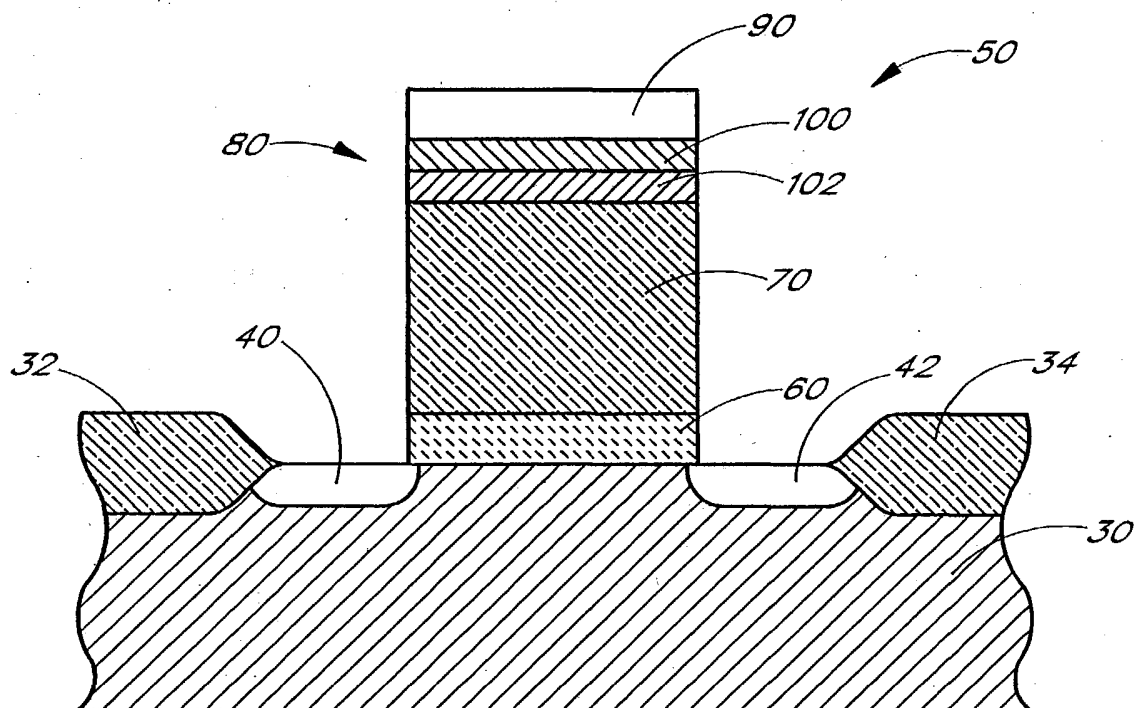


FIG. 3

SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED
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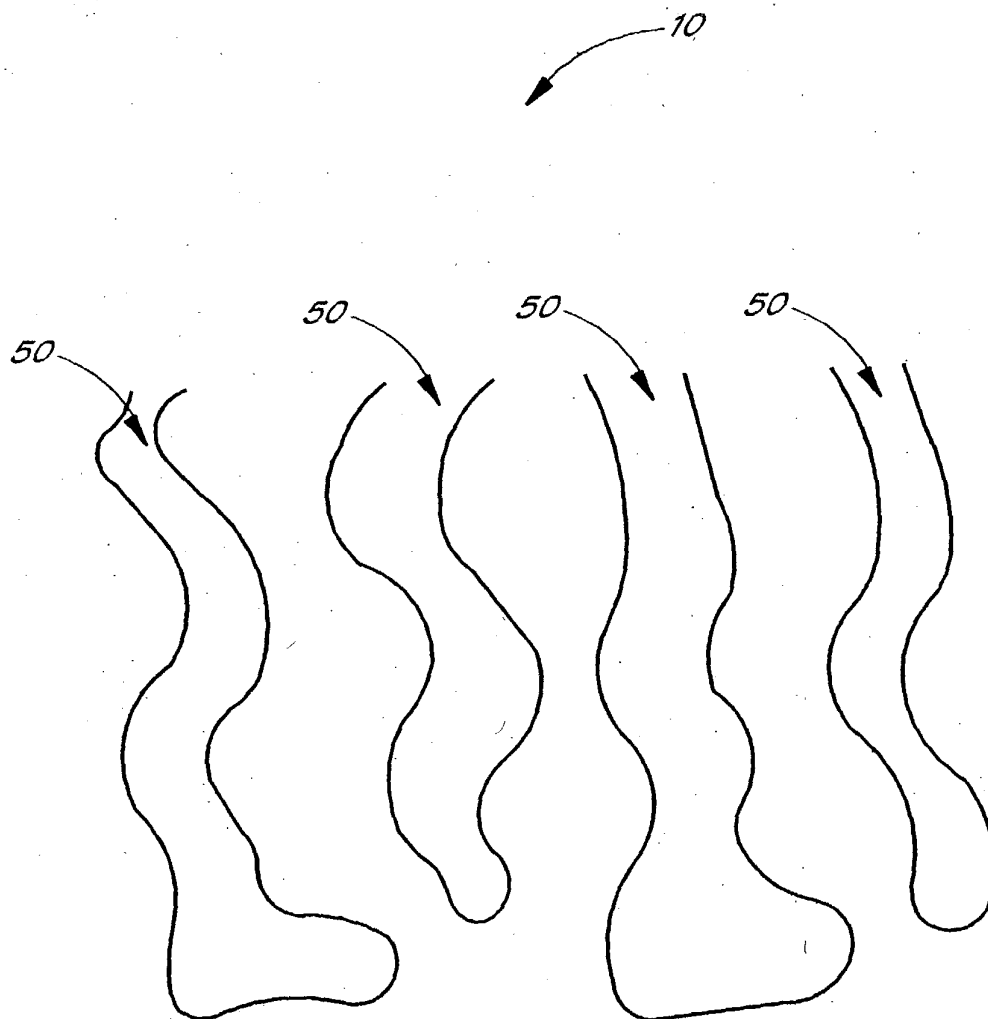


FIG. 4

SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED
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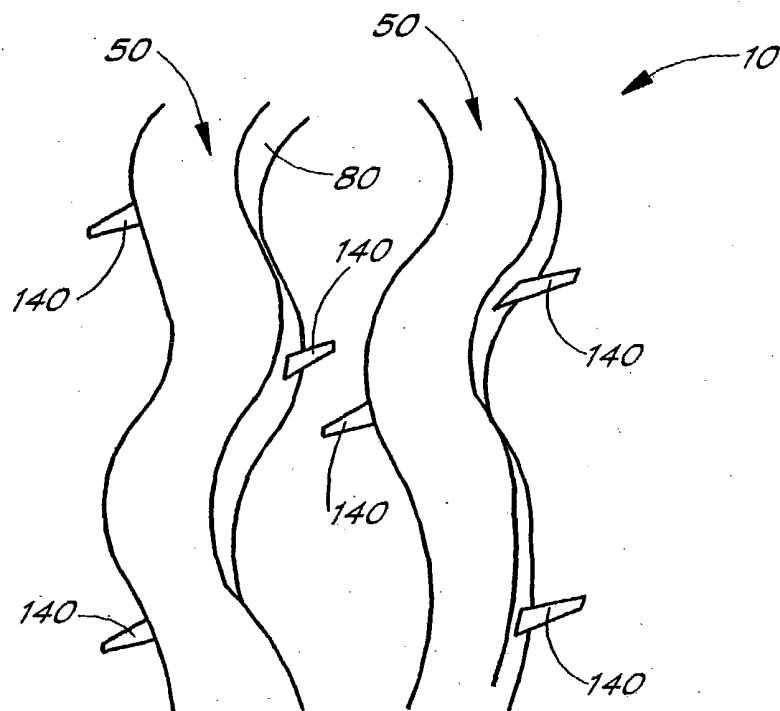
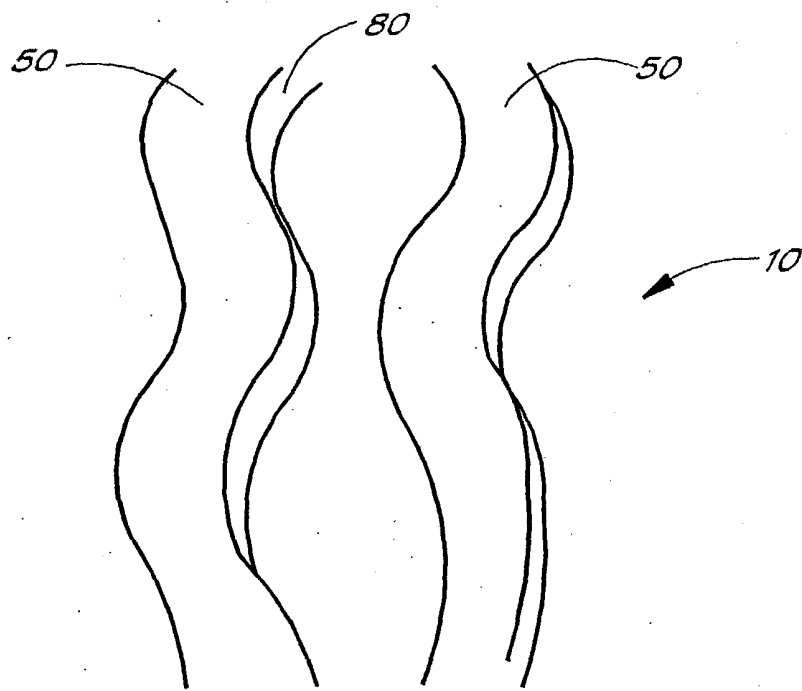


FIG. 5



SEMICONDUCTOR STRUCTURE WITH SUBSTANTIALLY ETCHED
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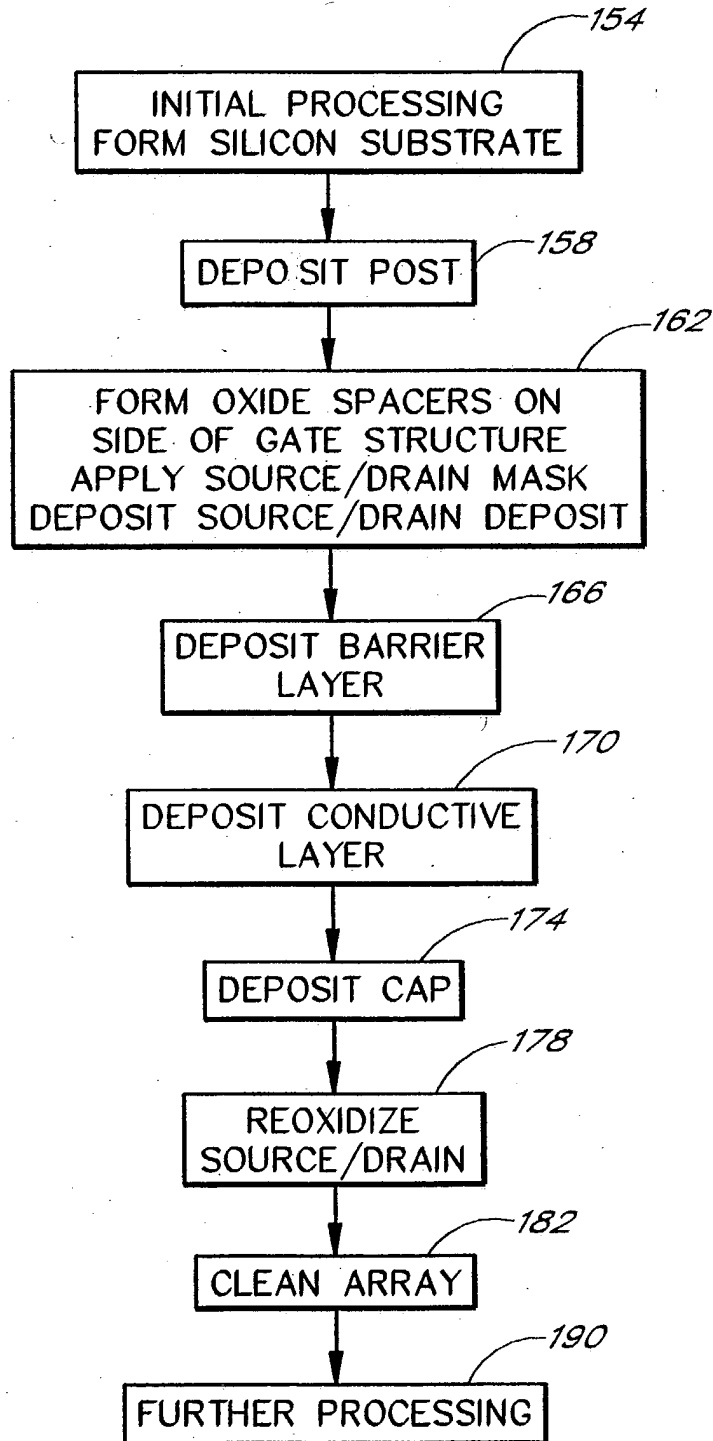


FIG. 7